

# Bridging the gap between semiconductor technology and design: a memory case study

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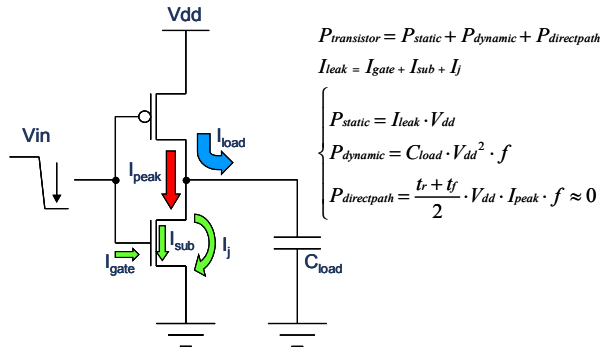
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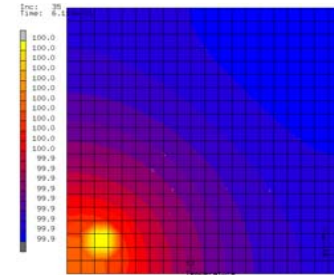


# ... beyond 100nm many technology issues become increasingly important

## Transistor leakage current increase power consumption

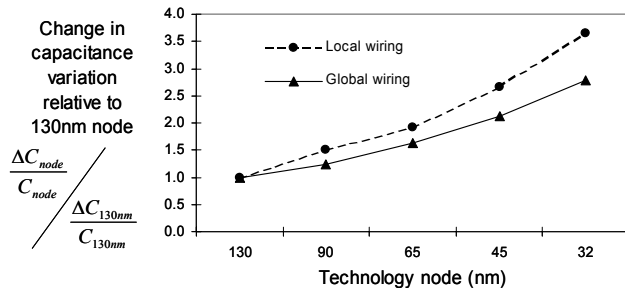


## Temperature driven dynamic process variations



## Increased static process variations with scaling

### Relative spread of capacitance due to technology

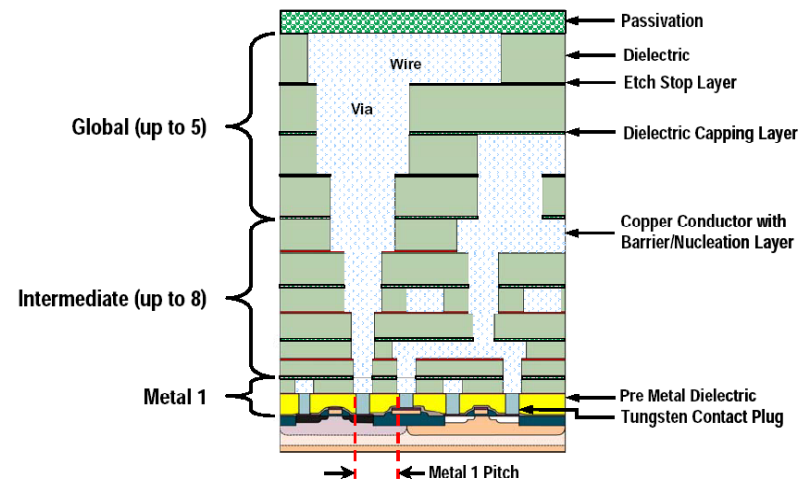


⇒ Relative spread in capacitance compared to 130 nm technology node (for dense wiring): increase of factor 2 in 65 nm node, factor 3.5 in 32 nm node

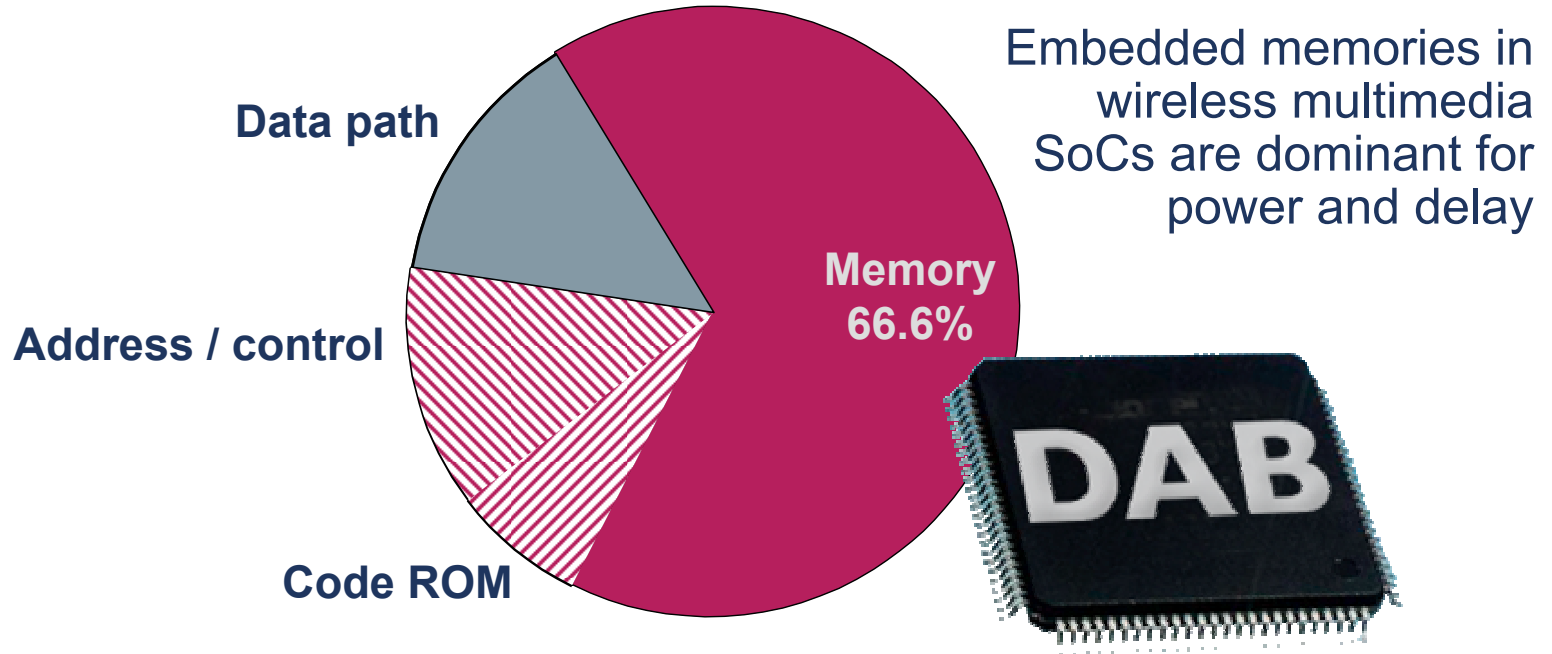
⇒ This is including the effect of CMP and roughness variation

## Capacitance and resistivity of local wires increases with scaling

## Global wires do not scale in length



# Memories dominate power consumption in data-dominated applications



The current focus of the TAD program is on SRAMs:

- SRAM is key element (energy and delay) in system (stand alone or embedded)
- Easy to model because regular and predictable topology (standard cell design with Place&Route in the flow is stochastic)
- Advantage for critical lithography and as technology driver (Layout rules are typically smaller than rest of components)

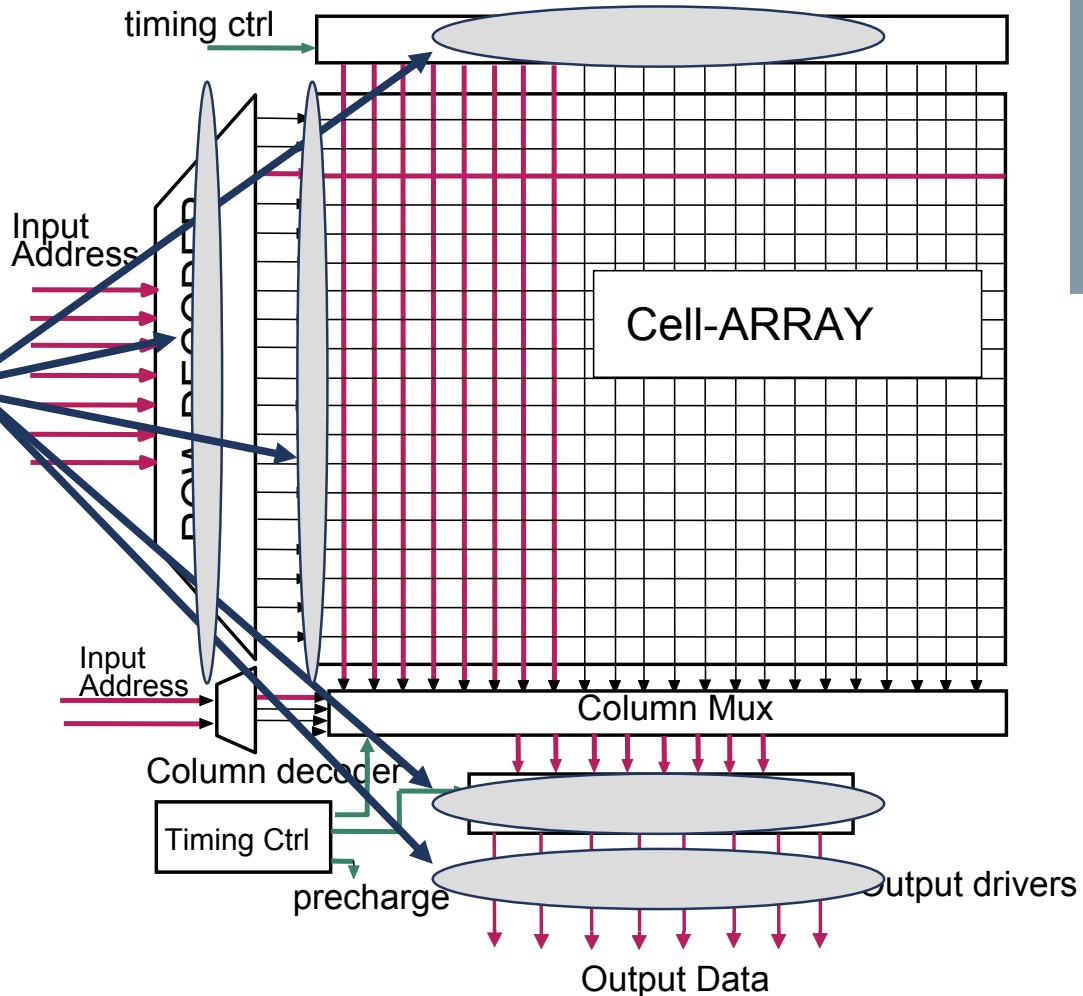
# Key element in new approach: “knobs” in memory to create Pareto trade-offs

Buffers/drivers needed/present in different parts of memory architecture

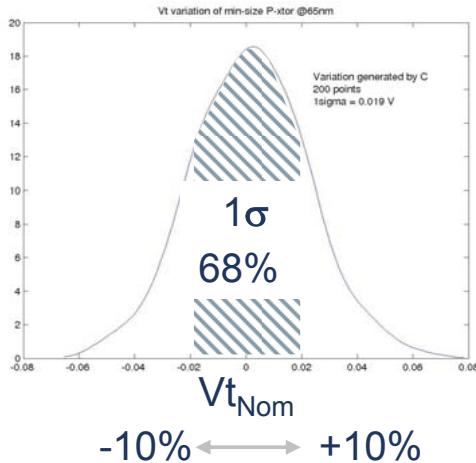
**Buffers**

Limited impact in area but big impact in energy/delay

Ideal components for cheap Pareto “Config knobs”

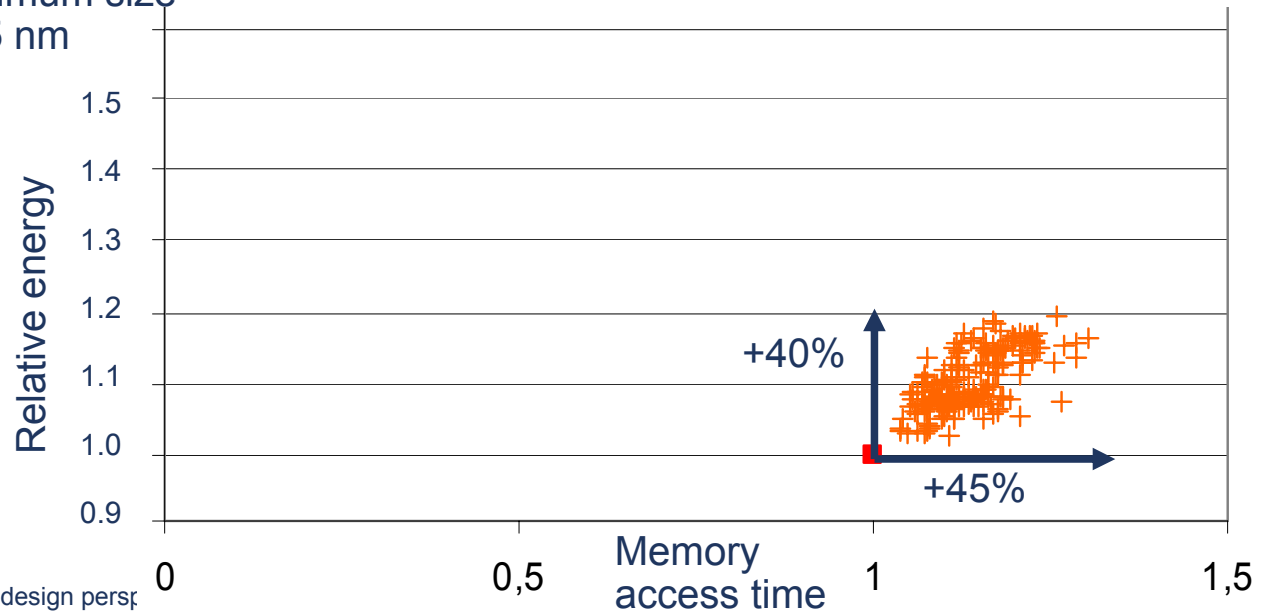


# IMEC's concept combines 100% (parametric) yield with variation tolerance

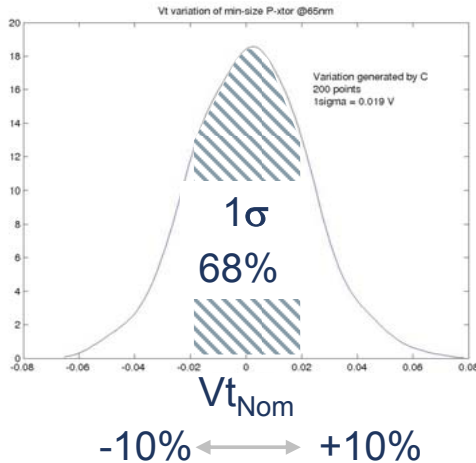


A moderate 10% variation for one transistor leads to 40% variation in access time for a 1KB memory

Variation for minimum size  
TOR @ 65 nm



# IMEC's concept combines 100% (parametric) yield with variation tolerance

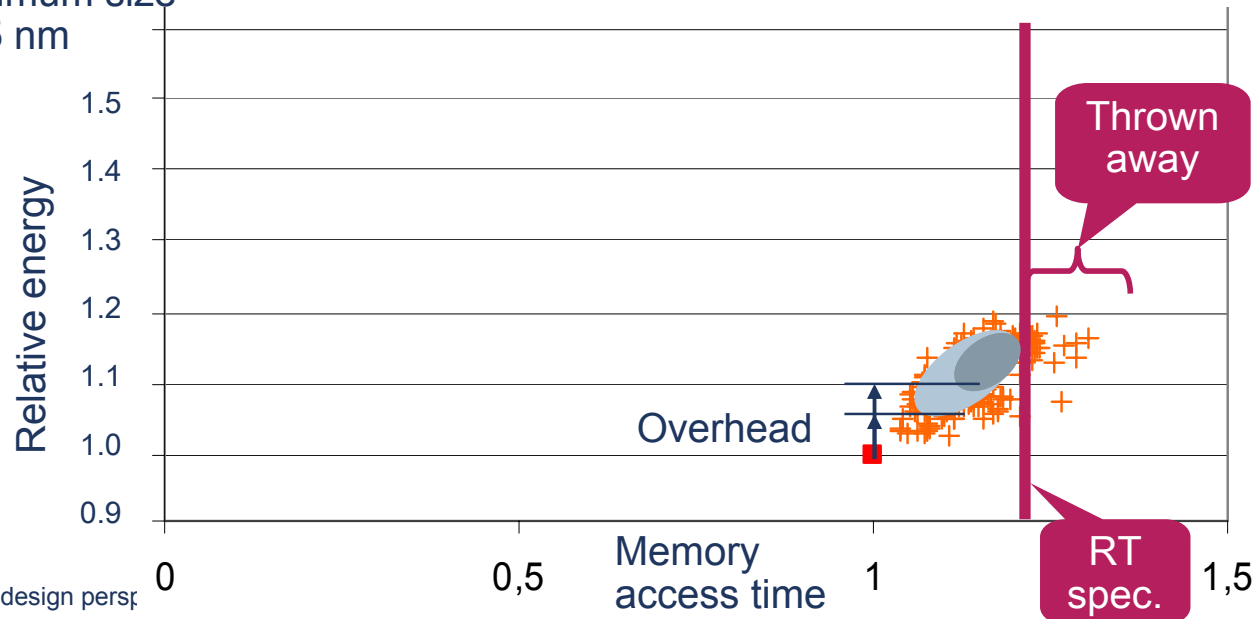


A moderate 10% variation for one transistor leads to 40% variation in access time for a 1KB memory

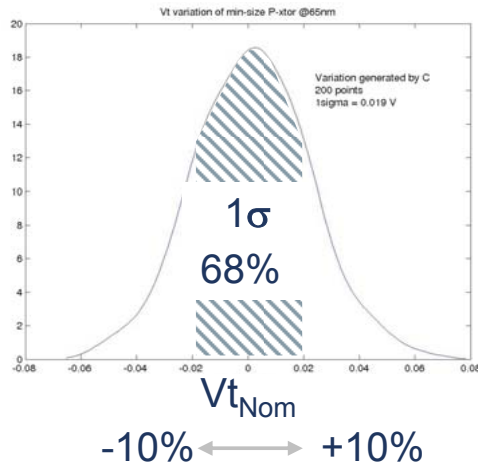
Sigma-based design improves (parametric) yield at the cost of performance-power overhead (design margins)

Sigma-based design badly scales: new silicon nodes have higher variation and hence more overhead needed

Variation for minimum size TOR @ 65 nm



# IMEC's concept combines 100% yield with variation tolerance



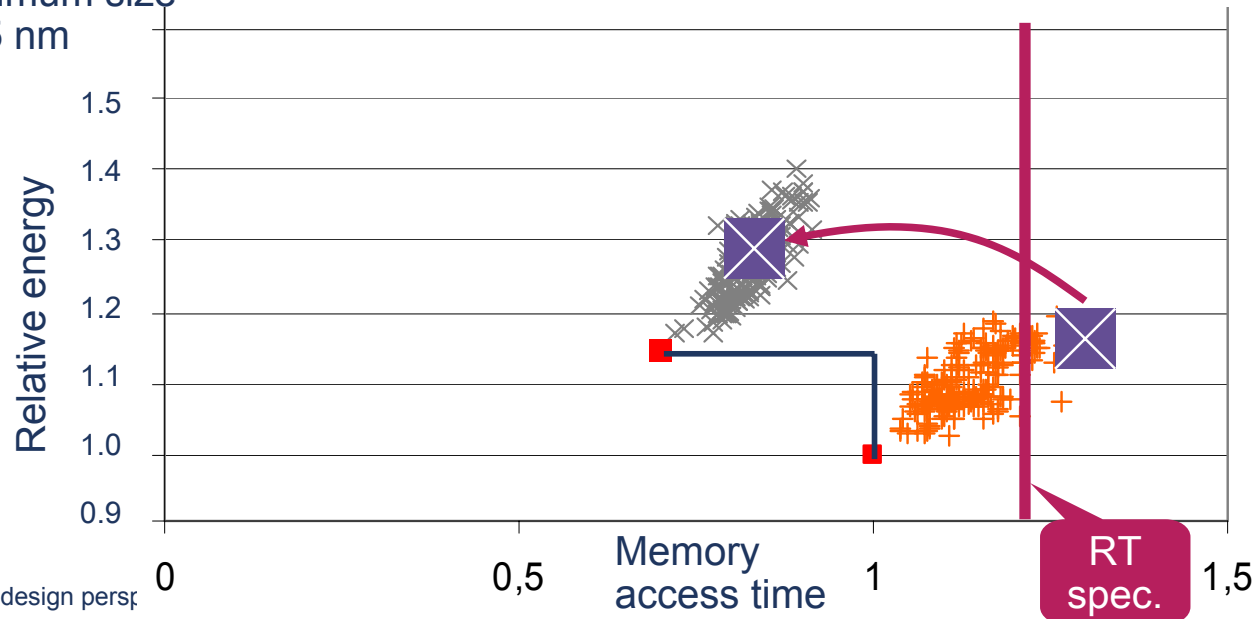
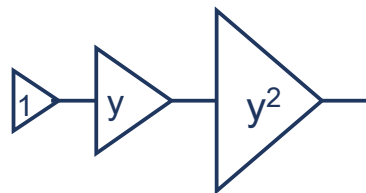
Variation for minimum size  
TOR @ 65 nm

A moderate 10% variation for one transistor leads to 40% variation in access time for a 1KB memory

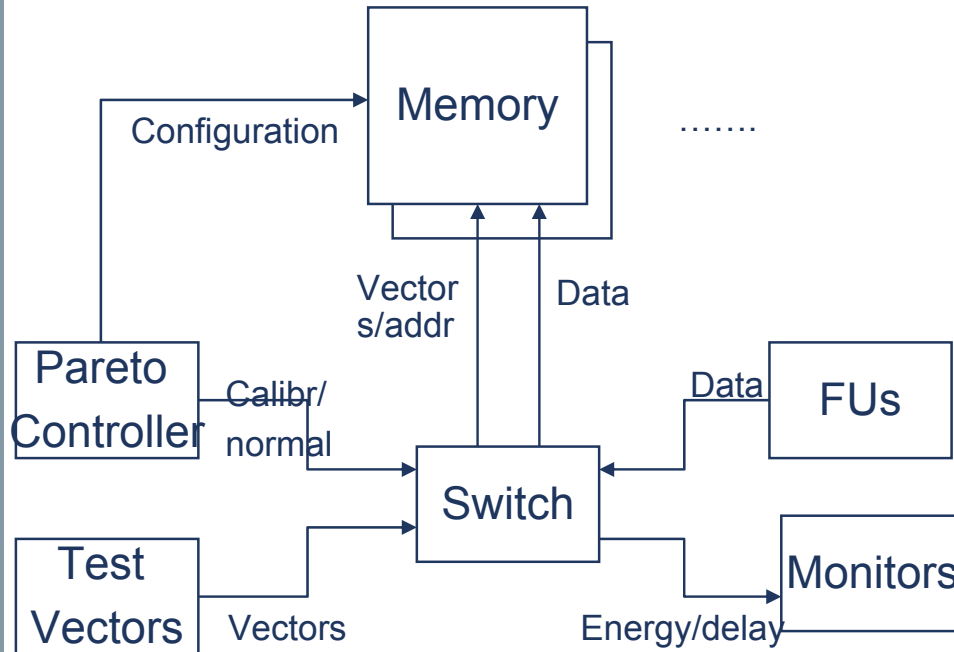
Sigma-based design leads to low yield and overhead

Sigma-based design badly scales: new silicon nodes have higher variation and hence more overhead

Better solution: just live with the speed you get & for those falling outside the spec, switch to a different/faster implementation, e.g. by using an additional driver step



# System requirements: run-time Pareto controller and calibration loop



Calibration (rarely): Per memory:

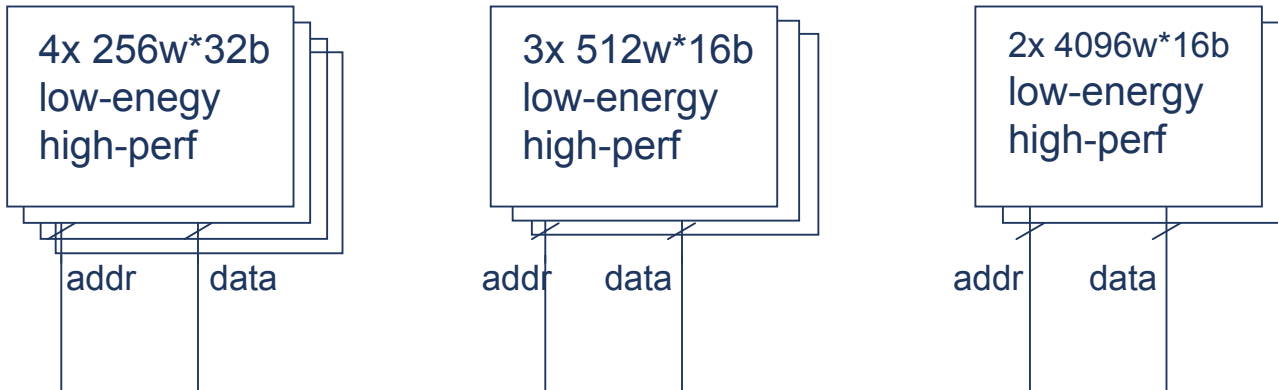
1. Apply Test vectors
2. Measure E/D
3. Overwrite Pareto tables

Normal operation:

1. Determine Pareto operating point for all mems in Pareto controller
2. Steer configuration knobs in memories



# Approach is applied to the memory organisation in a DAB application

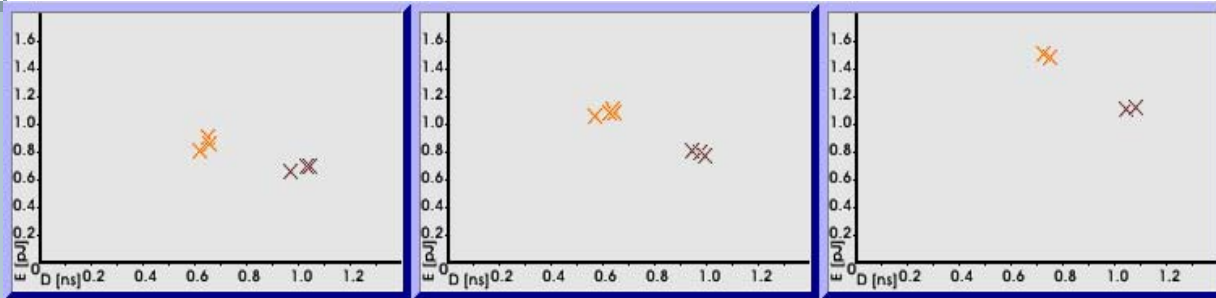


(Power) optimized communication network (with switches)

Base Implementation: 7 x 1KByte (16+32bit)+ 2 x 8KByte SRAMs with two configurations “knobs” each for Pareto trade-offs (low-energy and high-performance)



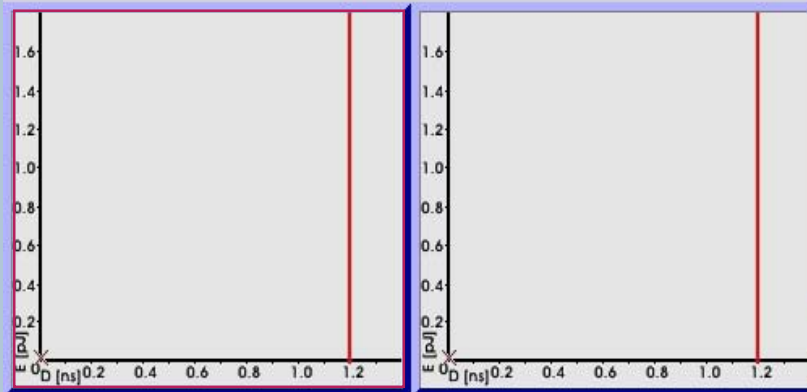
# DEMO - DAB: illustration of system level adaptation to process variability



512x16 memories

256x32 memories

4096x16 memories



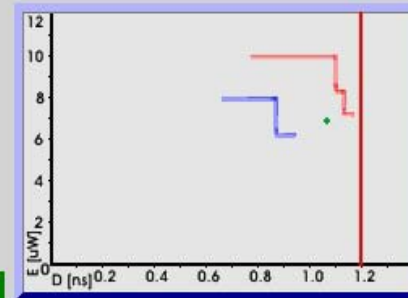
next to last changed configuration

last changed configuration

Delay(0) or energy(1):

Constraint value:

**Constraint of 1.2 ns has been met!**



memory architecture

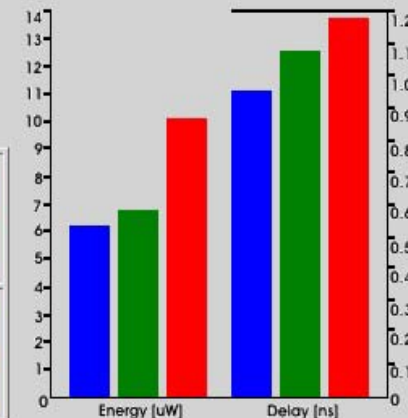
legend:

used configuration unused configuration

Energy/Delay:

nominal  
current  
worst  
constraint

selected configuration	512x16 nr.0	512x16 nr.1	512x16 nr.2	256x32 nr.3	256x32 nr.4	256x32 nr.5	256x32 nr.6	4096x16 nr.7	4096x16 nr.8
back-up configuration	512x16 nr.9	512x16 nr.10	512x16 nr.11	256x32 nr.12	256x32 nr.13	256x32 nr.14	256x32 nr.15	4096x16 nr.16	4096x16 nr.17



## Problem:

- Small on-chip SRAM is critical component (L1-memories)
- Impact process variability at SRAM level much more dramatic than transistor (from 10% to 50%)
- Industry → sigma-based design minimizes variability but trade-off yield and generates overhead (critical for L1-memories)

## Alternative:

- Use best case SRAM design tolerating variability with 100% yield (functionality still tested)
- Provide configuration “knobs” offering wide range of energy/delay trade-offs
- Let system compensate for eventual drift in variability at architecture level (system timing and not clock cycle based)

## Feasibility:

- Concept demonstrated in DAB receiver at SPICE level



SEEDS FOR TOMORROW'S WORLD **IMEC**NOLOGY

